

ABSTRACT

A pattern comparison inspection apparatus comprises:  
a reference position selecting portion (41) which selects  
5 from among positions on an inspection target pattern a  
reference position which is judged whether it should be  
contained in an inspection region; an image comparing  
portion (42) which compares an image signal at the  
reference position with an image signal at a position  
10 located an integral multiple of a repeat pitch away from  
the reference position; and an inspection region setting  
portion (43) which sets the inspection region by  
containing therein the reference position when a  
comparison result from the image comparing portion shows  
15 a value not greater than a prescribed threshold value.  
Thus, in the pattern comparison inspection apparatus  
which performs inspection for a pattern defect by  
comparing repeated patterns with each other in the  
inspection target pattern having a repeated pattern  
20 region, the inspection region can be enlarged within the  
bounds of the repeated pattern region.